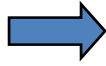



Typical Etch Recipes

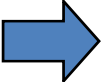
Standard Recipes

- **CF4 / O2**
- CHF3 / O2
- C2F6 / O2
- CF4 / Ar / H2
- CF4 / CHF3 / O2
- C2F6 / CHF3 / O2




Oxide
Nitride
Oxynitride
Quartz
Glass

- **O2**  1813, 3012, PMMA, ZEP

- **Cl2**
 - Cl2 / Ar
- 
- LPCVD Si**
PECVD Si
Bulk Si

- **Cl2 / CF4 / Ar**  **Cr / Au**

- **SF6 / O2 / Ar**  **LPCVD Si**
PECVD Si
Bulk Si

Oxide Recipe

- Gases:
 - CF4: 45 sccm
 - O2: 5 sccm
- Power: 350 watts
- Pressure: 150mT
- Etch Rate: ~1500 Å / min

Si Recipe

- Gases:
 - Cl2: 20 sccm
- Power: 200 watts
- Pressure: 10mT
- Etch Rate: ~900 Å / min

Nitride Recipe

- Gases:
 - CF4: 45 sccm
 - O2: 5 sccm
- Power: 350 watts
- Pressure: 150mT
- Etch Rate: ~1100 Å / min

GaAs Recipe

- Gases:
 - Cl2: 20 sccm
- Power: 250 watts
- Pressure: 10mT
- Etch Rate: ~4500 Å / min